

Retreat on XFEL Sciences

X-ray Optics: Introduction

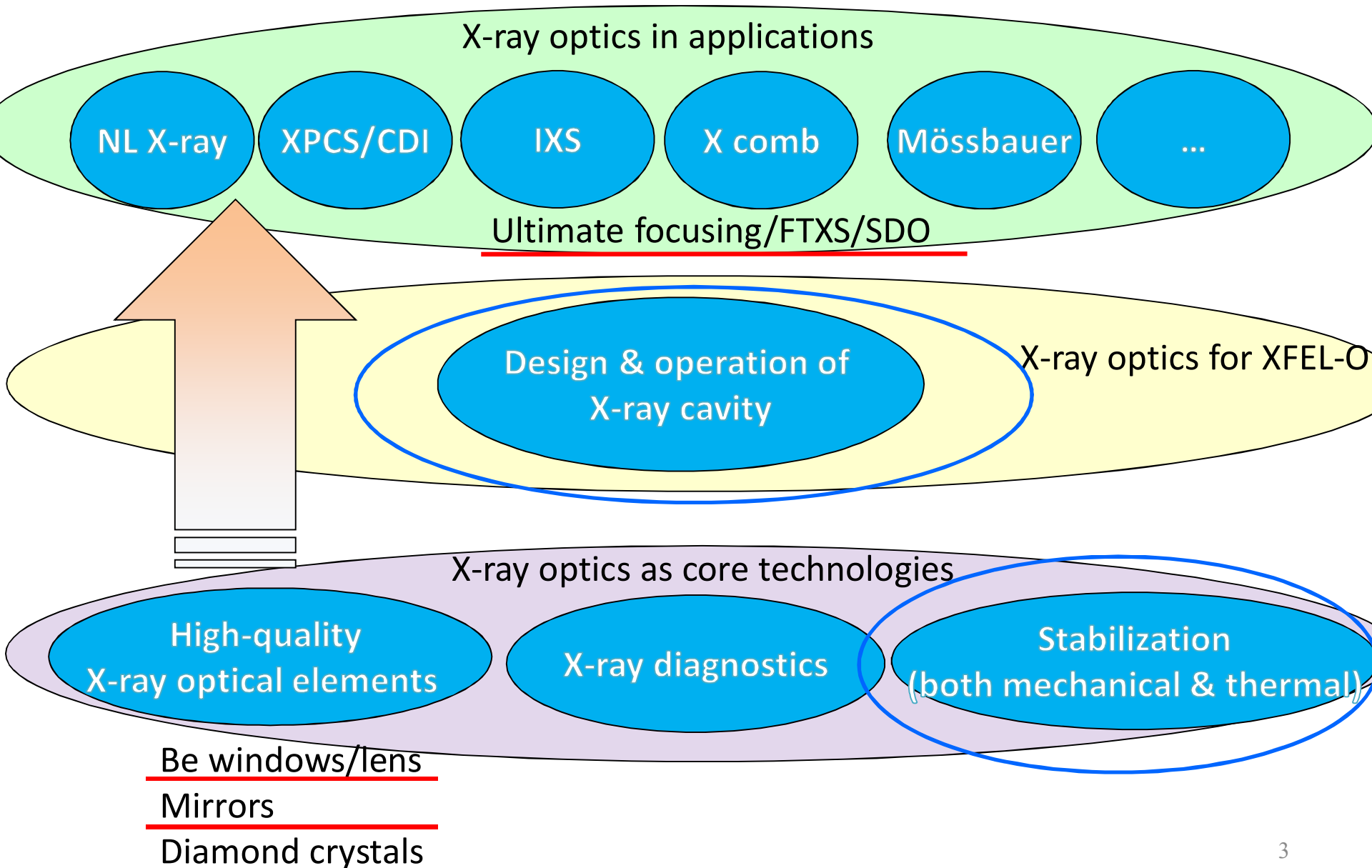
Makina Yabashi & Yuri Shvyd'ko

June 30, 2016 @SLAC

Remarks

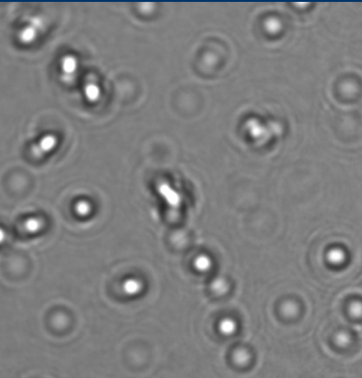
- **Ideal** light sources allows us to innovate x-ray optics & beamline devices in much **simpler** schemes; Chance to bring **new ideas**
- Synergy and distinction in XFEL-O, SASE-XFEL, and DLSR

Map on “X-ray optics”

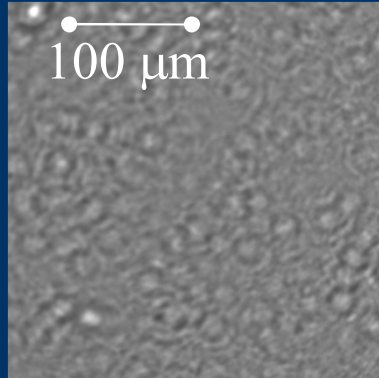


Speckle-free Be foils & mirrors

Be window

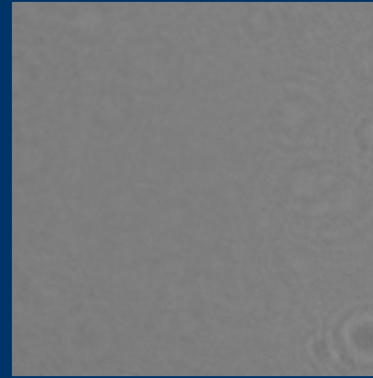


Polished O-30
(HIP powder foil)
100 nm p-v

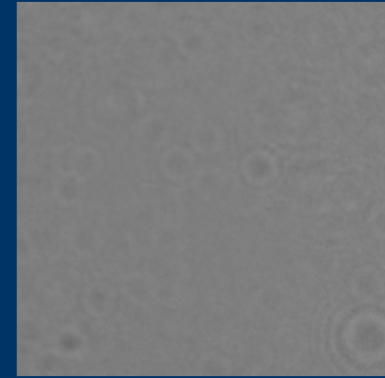


Polished IF-1
(Ingot foil)
100 nm p-v

Goto et al. Proc. SRI 2007, 1057



Polished PVD
50 nm p-v



Kapton



$t \sim 50 \mu\text{m}$: thicker foils under development

Mirror

Mori et al. Proc. SPIE 2001, 30

4

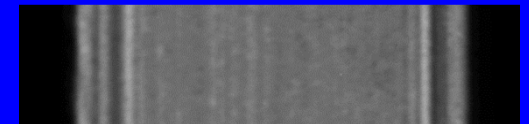
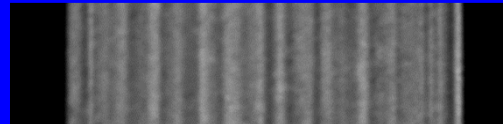
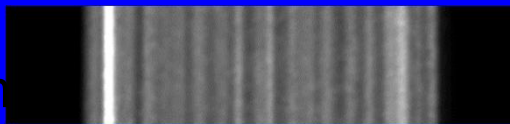
Distance:

Pre-machined

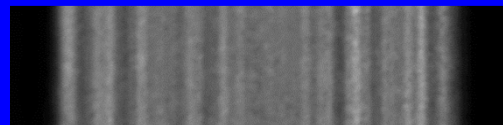
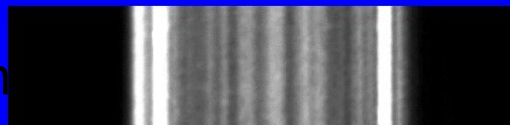
PCVM

PCVM+EEM

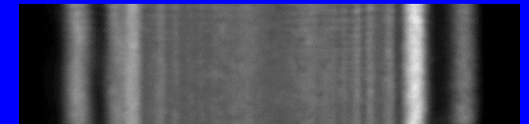
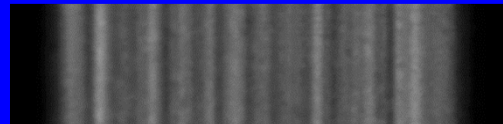
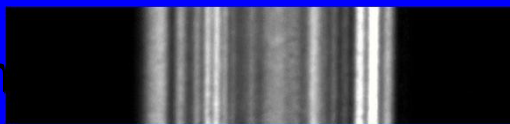
166 mm



566 mm



966 mm

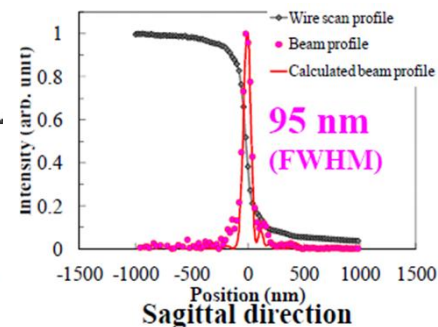
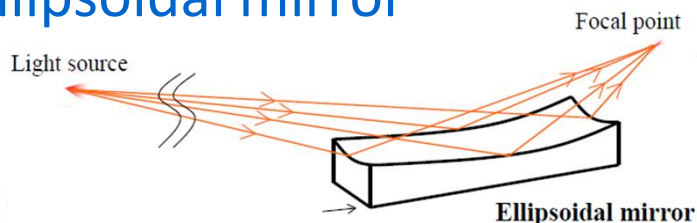


Recent activities on mirror developments

Focusing/collimating

Adaptive KB optics

Ellipsoidal mirror

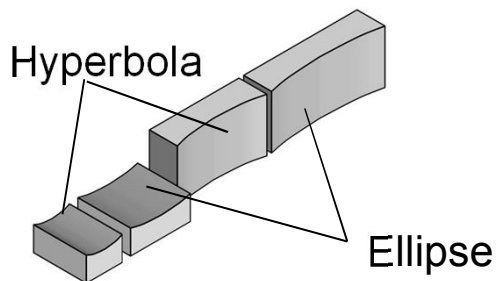


Yumoto-san
(SPring-8)

Imaging

Advanced KB

R. Kodama et al., *Optics Letters* (1996).



- Achromatic
- Wide FOV (Abbe sine condition)
- Sub-100 nm res



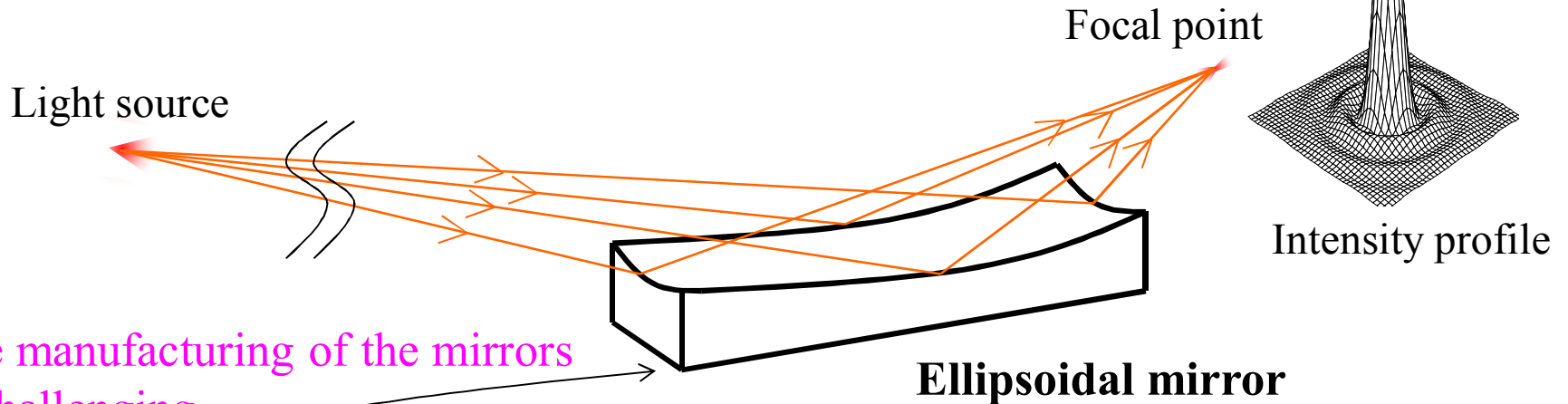
Matsuyama et al., OE 9746 (2015);
in preparation (2016) Osaka U

Wolter mirror

Electroforming
technique



Mimura et al.,
JPB **48** 244002 (2015)
U Tokyo

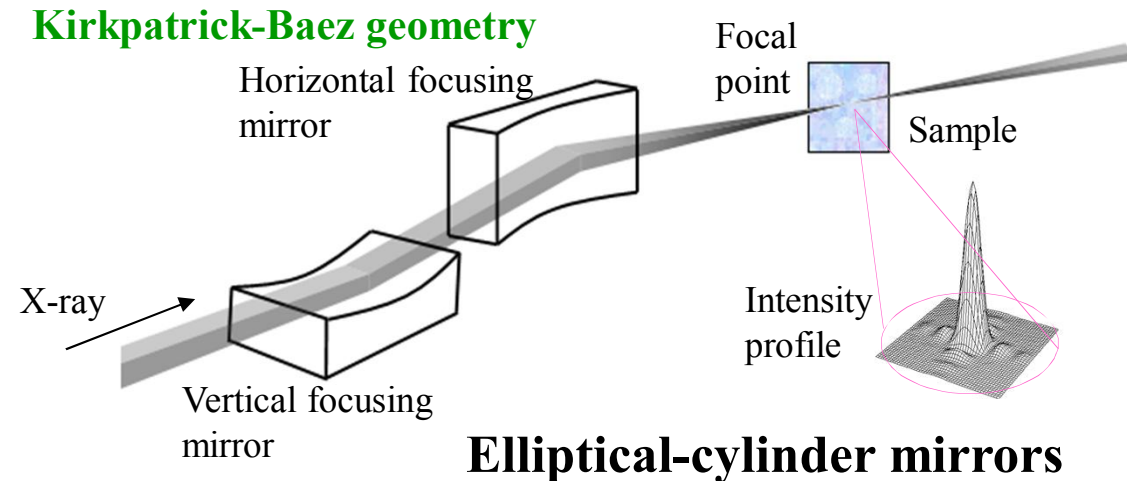


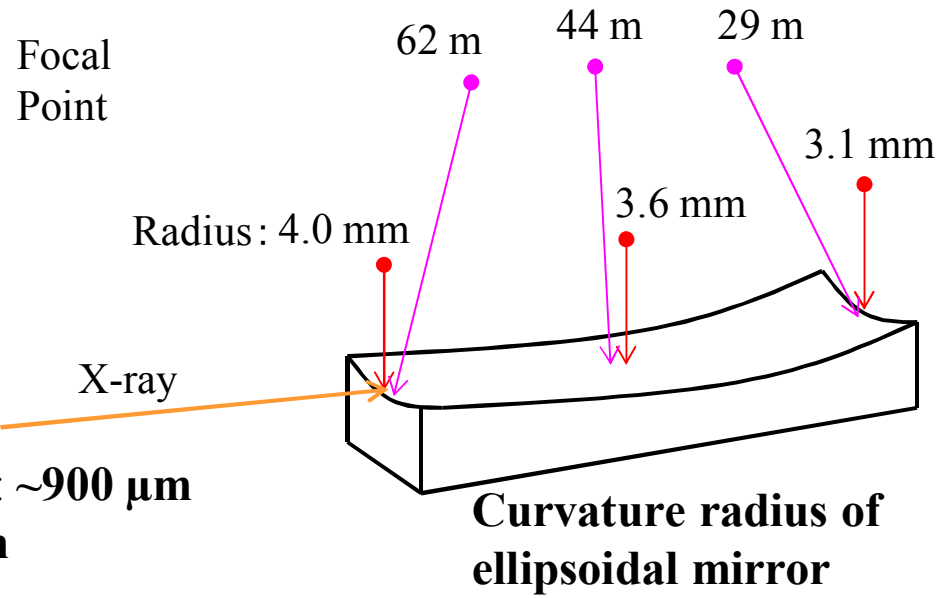
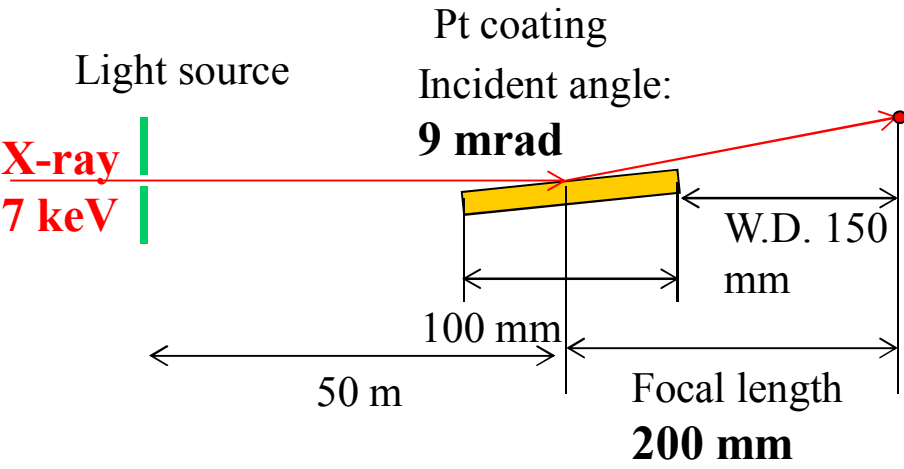
The manufacturing of the mirrors is challenging.

Advantage

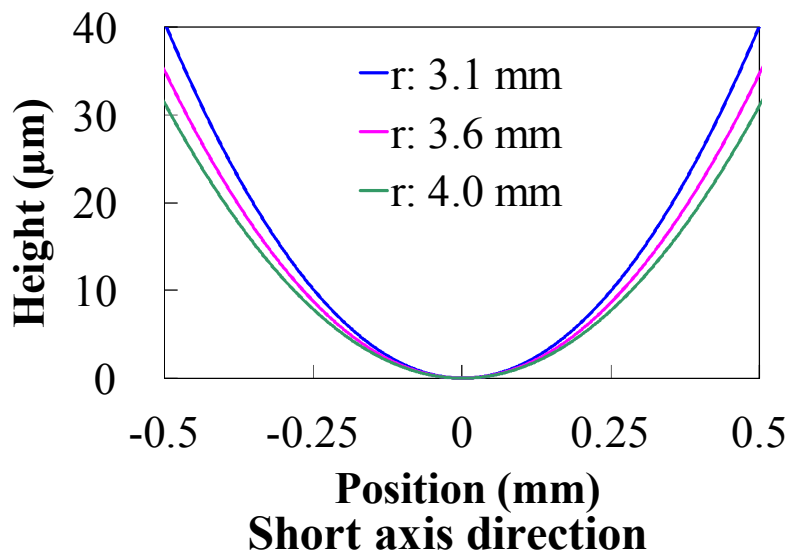
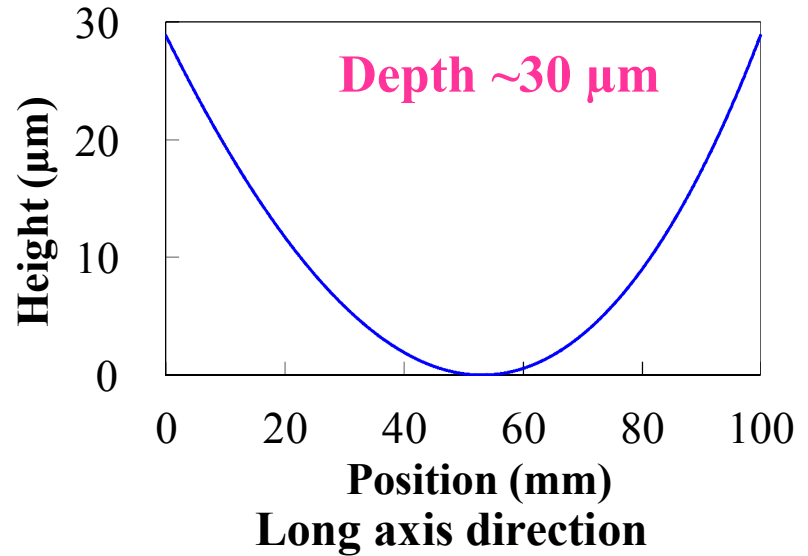
- High focusing efficiency
- Simple mirror manipulator
- Position stability improvement of focusing beam

Focusing device & collimator for many applications





Spatial acceptance in the longitudinal direction: **~900 μm**
 Diffraction-limited focusing beam size: **~35 nm**

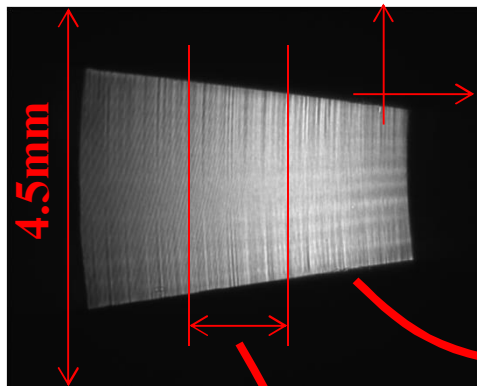


Surface profiles

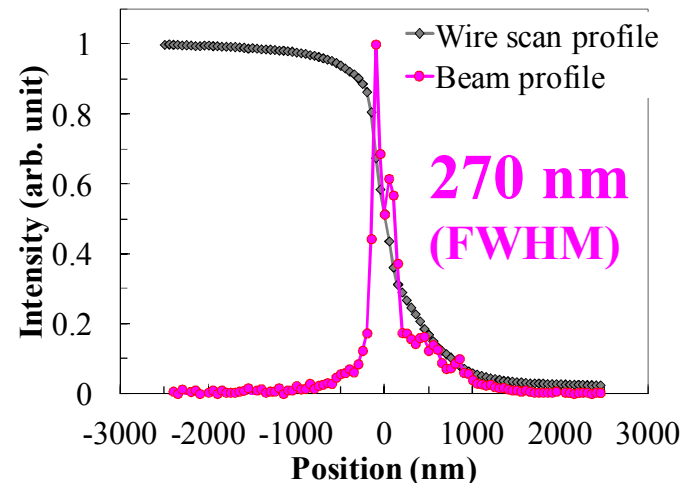
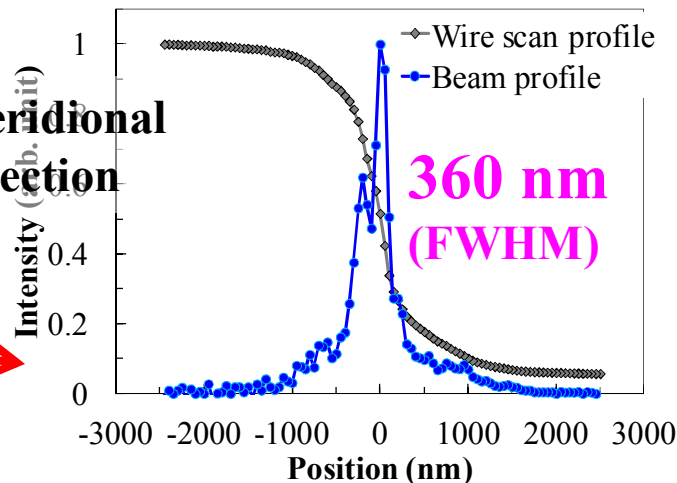
Measured focusing beam profiles at 7 keV

Sagittal direction

Full aperture: $0.45 \times 93 \text{ mm}^2$



Meridional direction

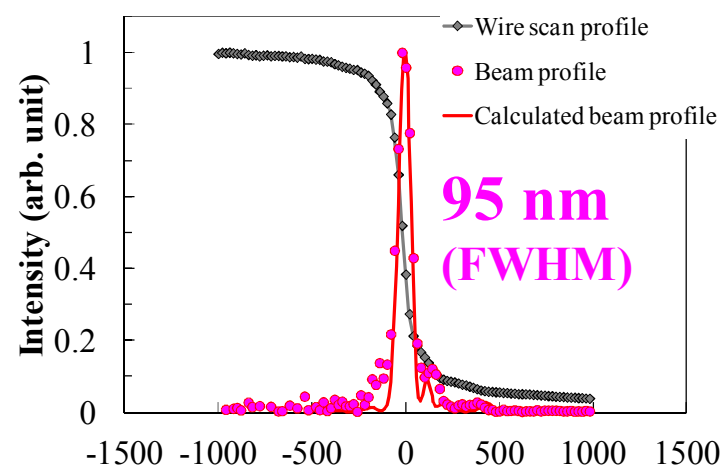
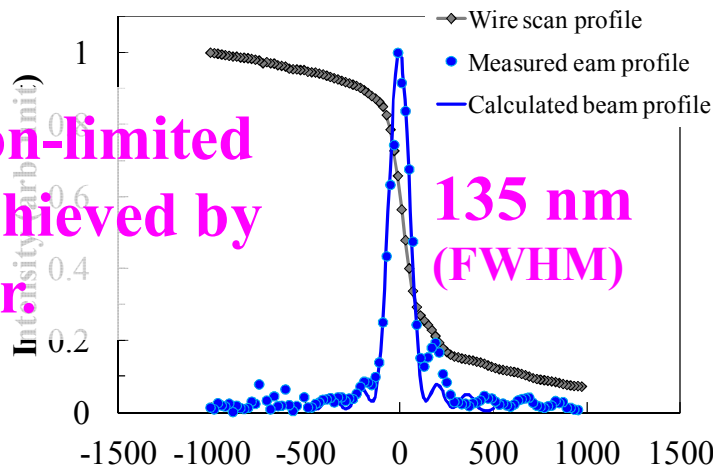


Reflection image (sector form)

Meridional direction

Sagittal direction

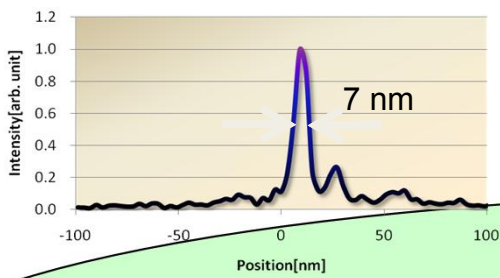
Sub-aperture: $0.45 \times 27 \text{ mm}^2$



Meridional direction

Sagittal direction

Nearly diffraction-limited focus size was achieved by ellipsoidal mirror



“X-ray Optics”

Applications

NL X-ray

XPCS/CDI

IXS

X comb

Mössbauer

Ultimate focusing/FTXS/SDO

XFEL-O

Design & operation of
X-ray cavity

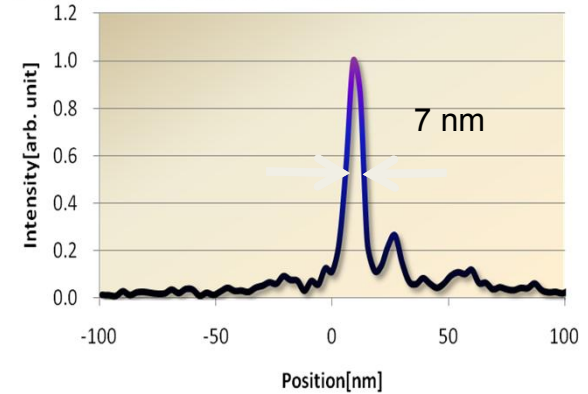
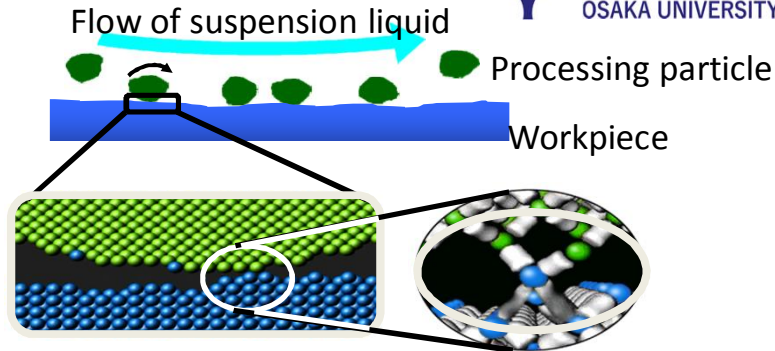
Core technologies on X-ray optics

High-quality
X-ray optical elements

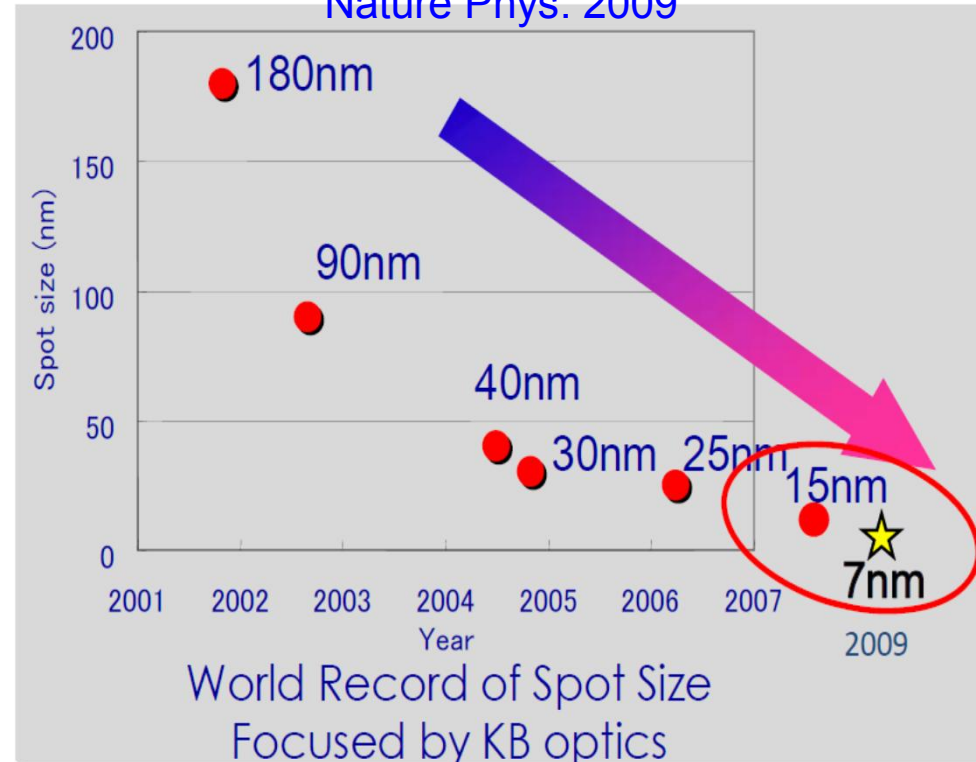
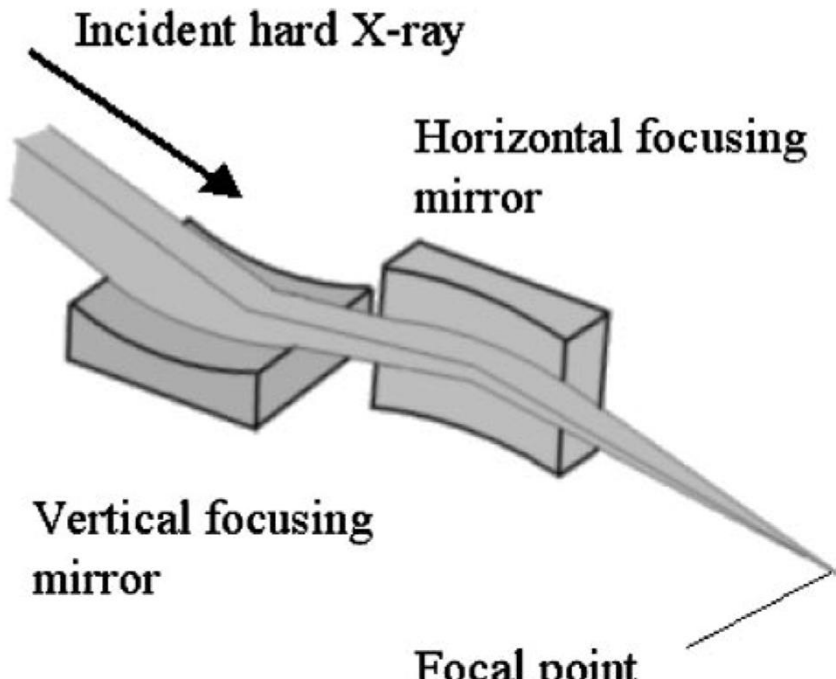
X-ray diagnostics

Stabilization
(both mechanical & thermal)

Ultimate focusing with mirrors



K. Mimura et al.
Nature Phys. 2009



Low divergent beam → limitation of NA

Simple focusing

WD becomes short

2 stage focusing

Focusing with enough NA and enough WD

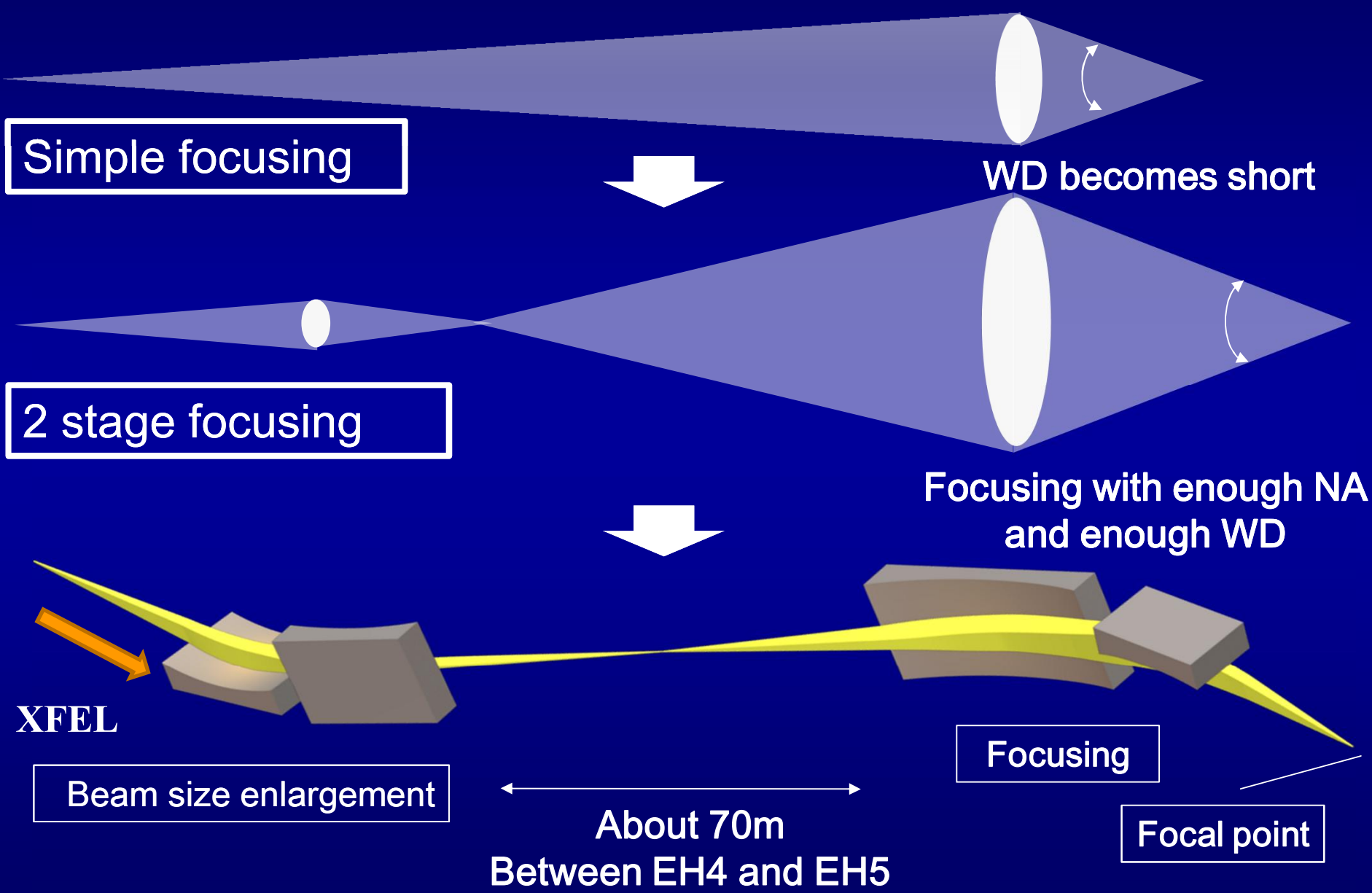
XFEL

Beam size enlargement

About 70m
Between EH4 and EH5

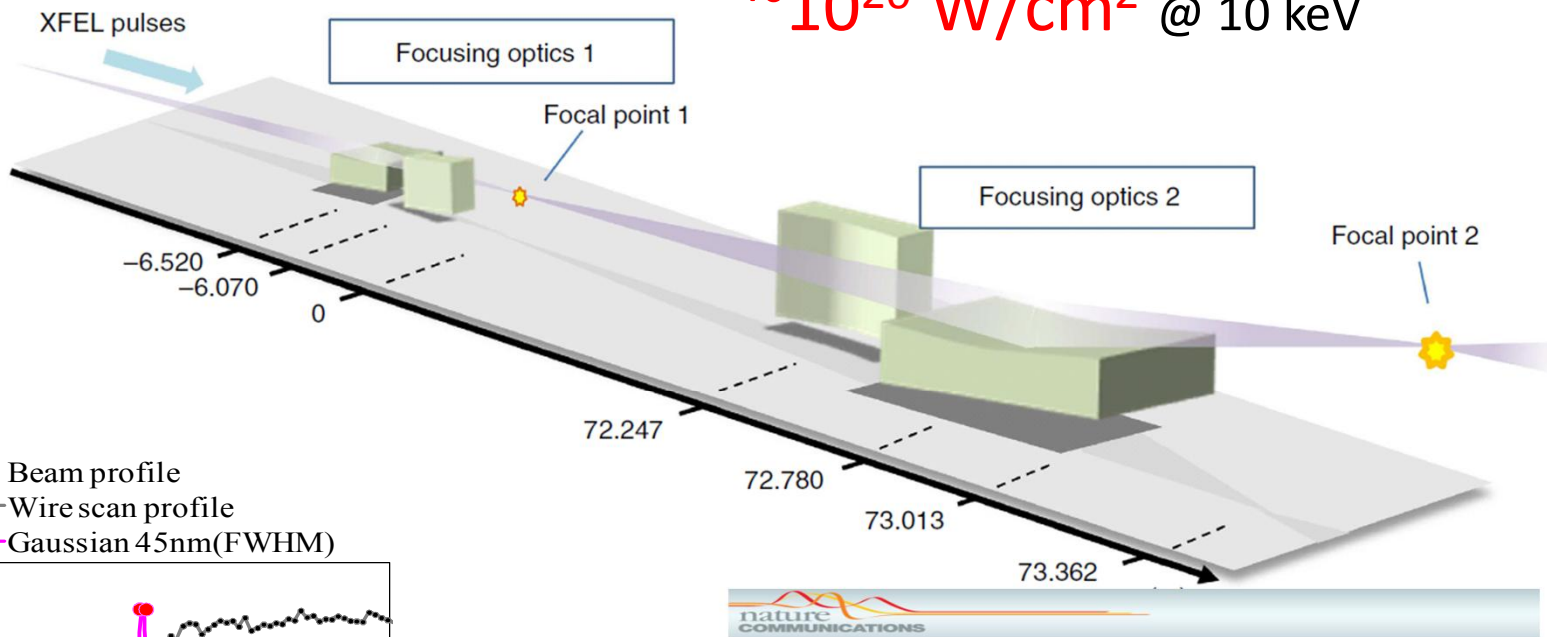
Focusing

Focal point

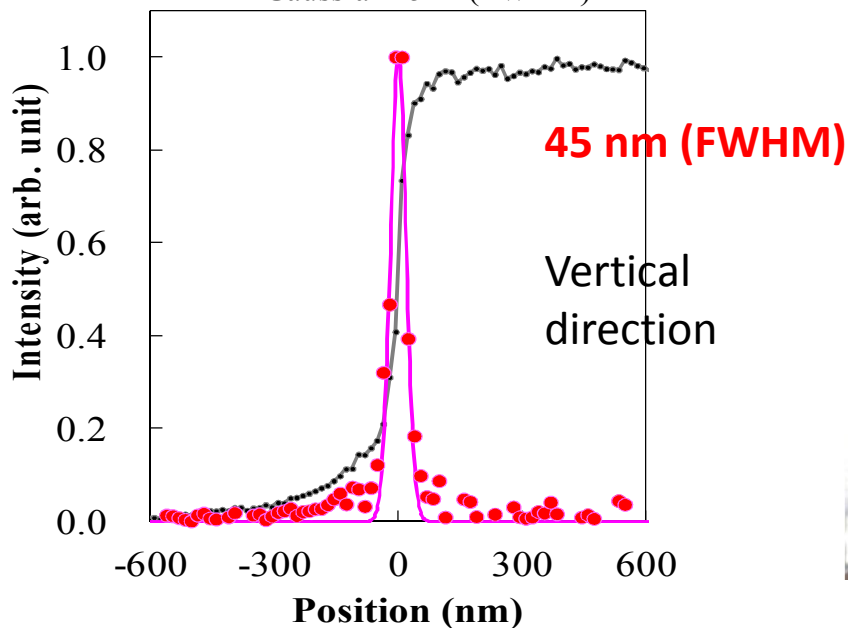


Two-stage focusing system

$\sim 10^{20} \text{ W/cm}^2$ @ 10 keV



- Beam profile
- Wire scan profile
- Gaussian 45nm(FWHM)



ARTICLE
Received 17 Sep 2013 | Accepted 4 Mar 2014 | Published 30 Apr 2014
DOI: 10.1038/ncomms5339
Generation of $10^{20} \text{ W cm}^{-2}$ hard X-ray laser pulses with two-stage reflective focusing system
Hidekazu Mimura^{1*}, Hirokatsu Yumoto^{2,*}, Satoshi Matsuyama^{3,*}, Takahisa Koyama², Kensuke Tono², Yuichi Inubushi⁴, Tadashi Togashi², Takahiro Sato⁴, Jangwoo Kim³, Ryosuke Fukui³, Yasuhisa Sano³, Makina Yabashi⁴, Haruhiko Ohashi^{2,4}, Tetsuya Ishikawa⁴ & Kazuto Yamauchi³

Mimura et al, Nature Commun 5 3539 (2014)



Mimura-san Yamauchi-sensei Ohashi-san Yumoto-san

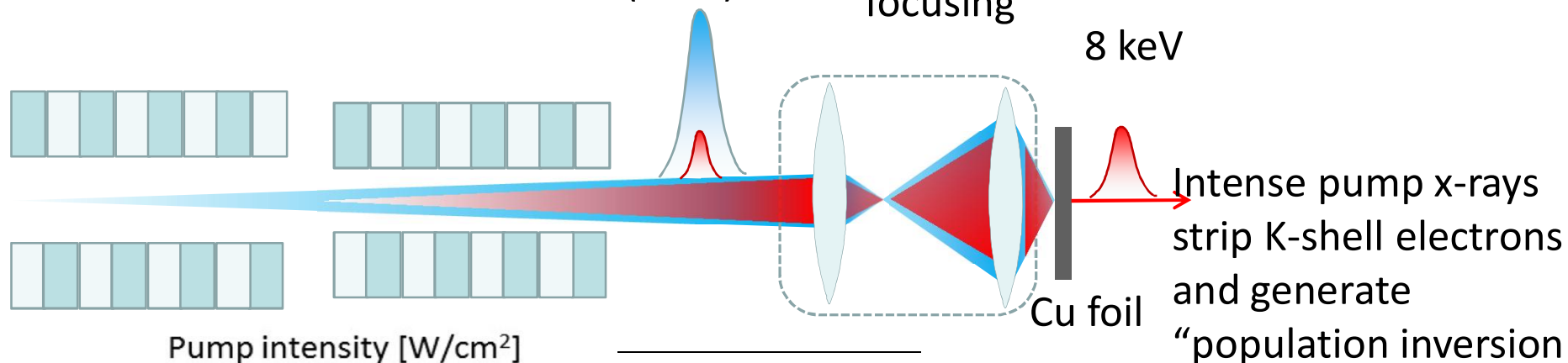
Cu K α atomic laser

Yoneda *et al.*,
Nature **524**, 446 (2015)

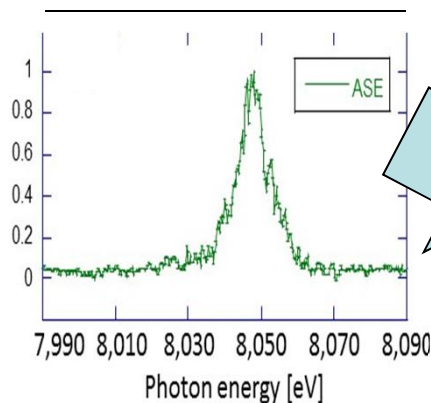
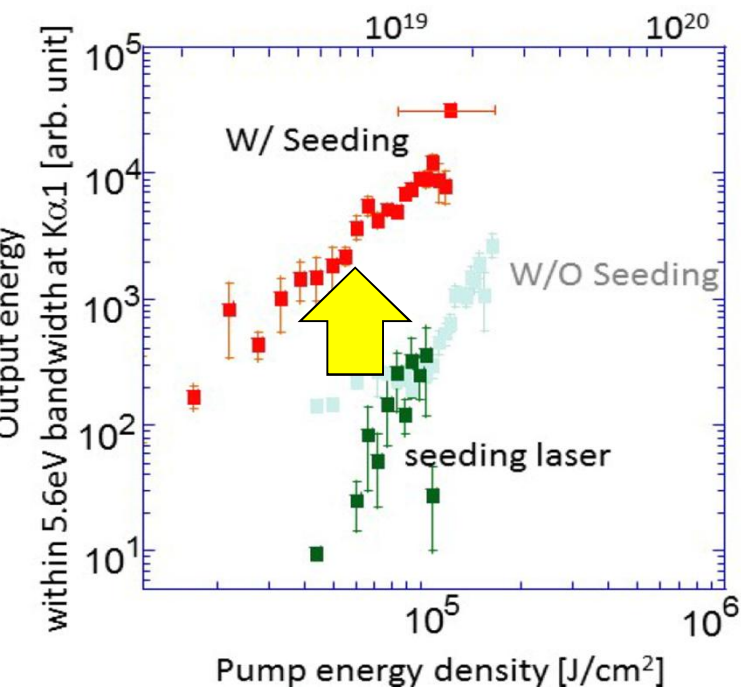
9 keV (pump) &
8 keV (seed)

Two-stage
focusing

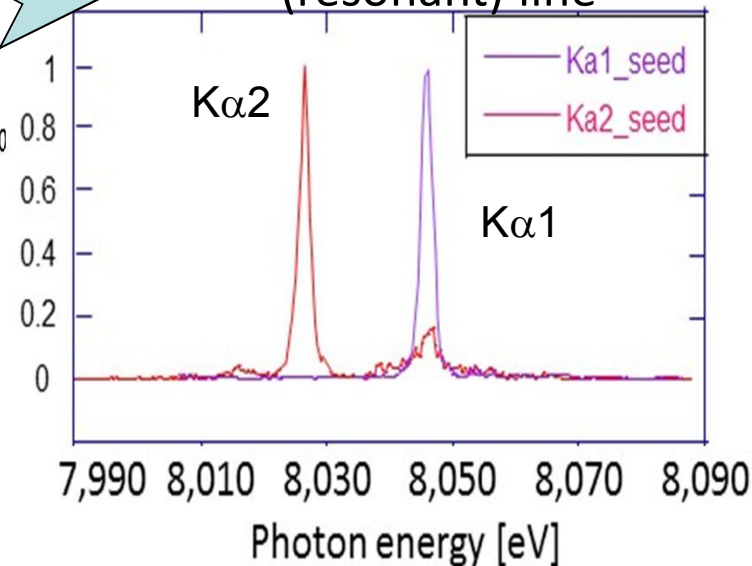
8 keV



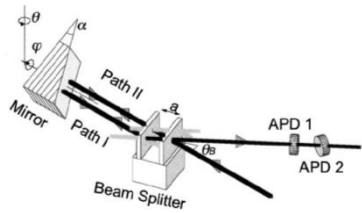
Pump intensity [W/cm²]



Amplification of K α
(resonant) line



“X-ray optics”



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X comb

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Mössbauer

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X-ray cavity

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X-ray diagnostics

Stabilization
(both mechanical & thermal)

FTXS

Tamasaku et al, APL 83 (2003) 2994

APPLIED PHYSICS LETTERS

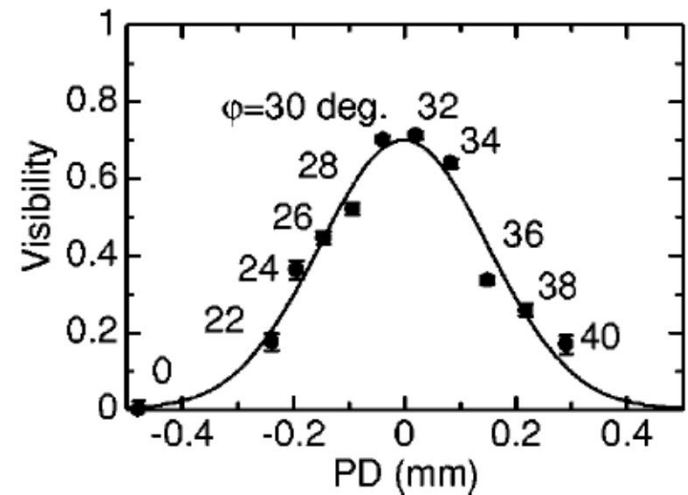
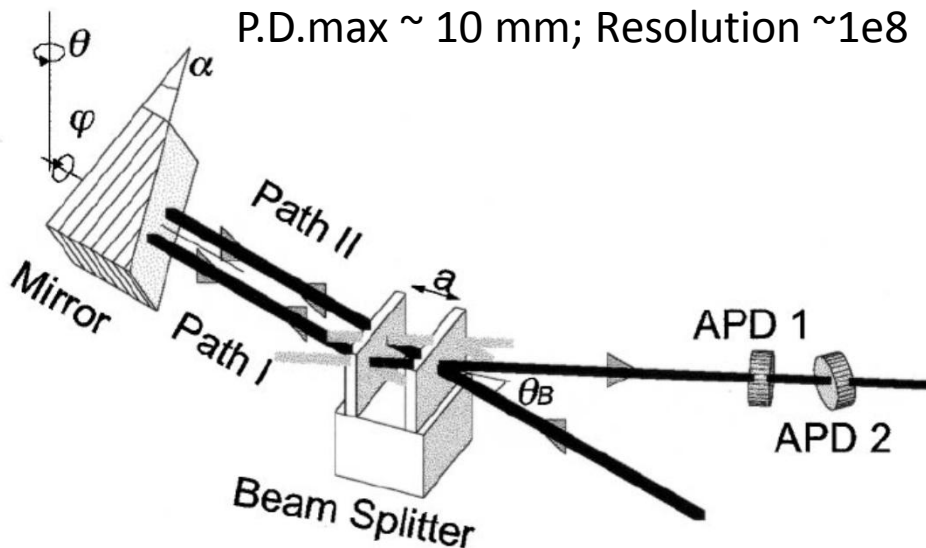
VOLUME 83, NUMBER 15

High-resolution Fourier transform x-ray spectroscopy

Kenji Tamasaku^{a)} and Tetsuya Ishikawa
SPring-8/RIKEN, Mikazuki, Hyogo 679-5148, Japan

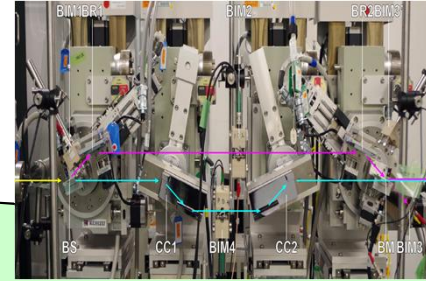
Makina Yabashi
SPring-8/JASRI, Mikazuki, Hyogo 679-5198, Japan

Si 14 6 0 @ 17.36 keV
P.D.max ~ 10 mm; Resolution ~1e8



Ultrafast pulse duration facilitates measurement of interferogram

“X-ray Optics”



Applications

NL X-ray

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Design & operation of
X-ray cavity

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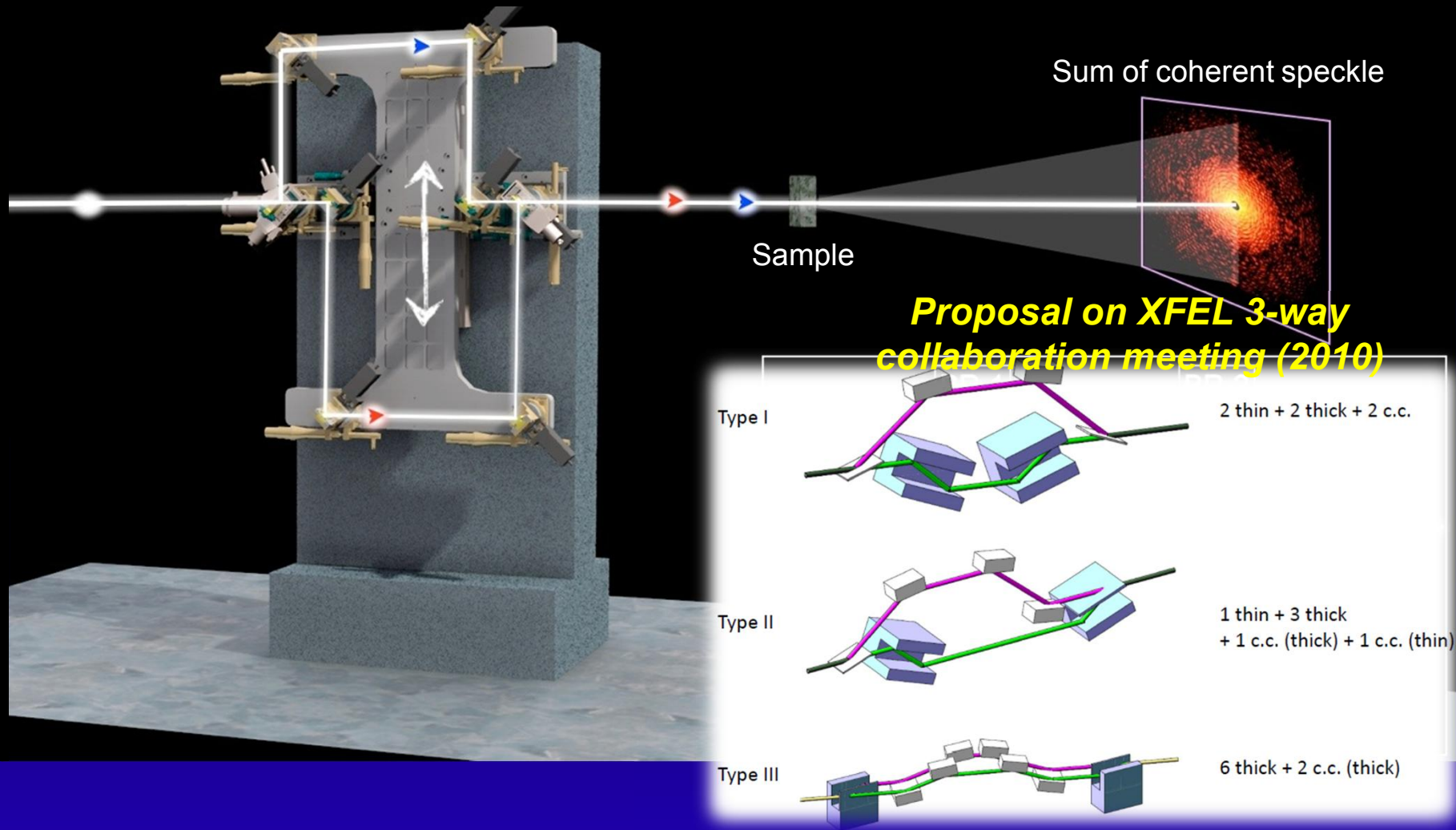
Stabilization
(both mechanical & thermal)

First split-and-delay optics for HX

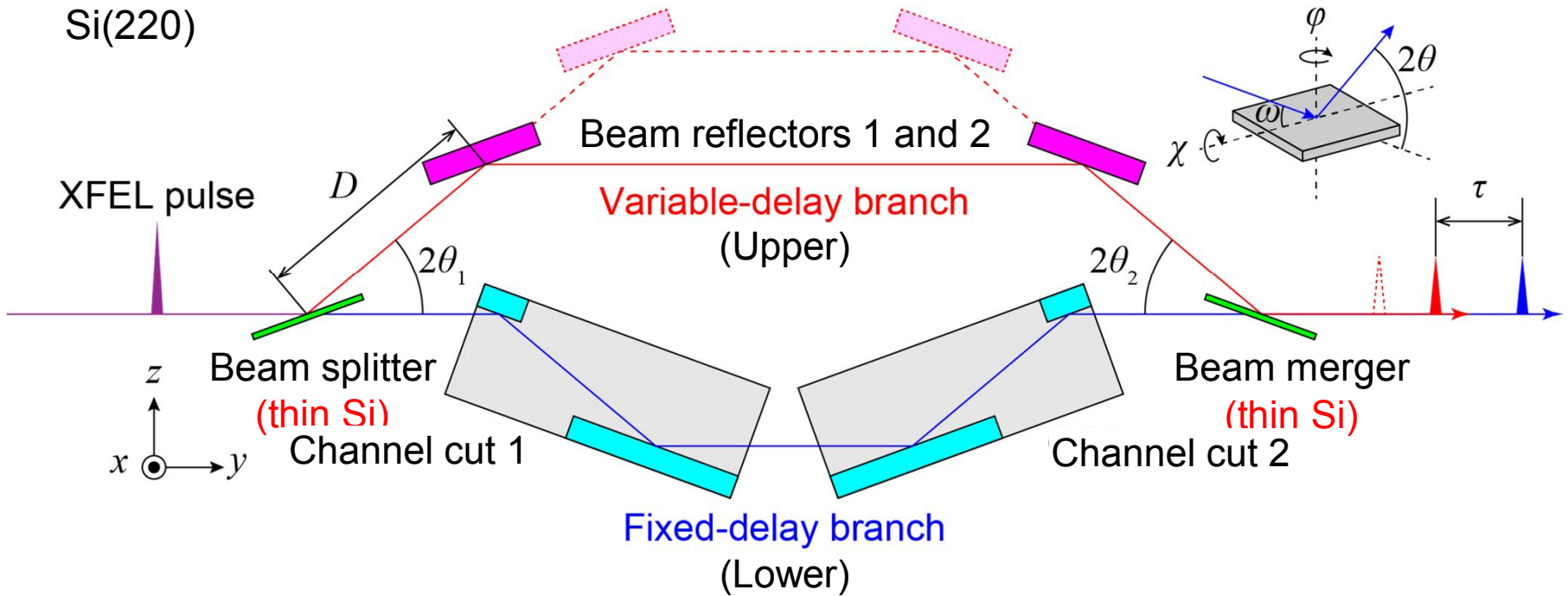
Courtesy of Gerhard Grübel

Based on **Bragg diffraction** and **90° scattering** with Si(511) or (422)

W. Roseker *et al.*, *Opt. Lett.*, **34** (2009).
W. Roseker *et al.*, *J. Synchrotron Rad.*, **18** (2011).
W. Roseker *et al.*, *Proc. SPIE*, **8504** (2012).



SDO configuration



Osaka-san
(Osaka U → SACLA)

Crystal diffraction:

Large time delays ($>ps$)
High energy resolutions ($\Delta E/E < 1 \times 10^{-4}$)

Two independent delay branches:

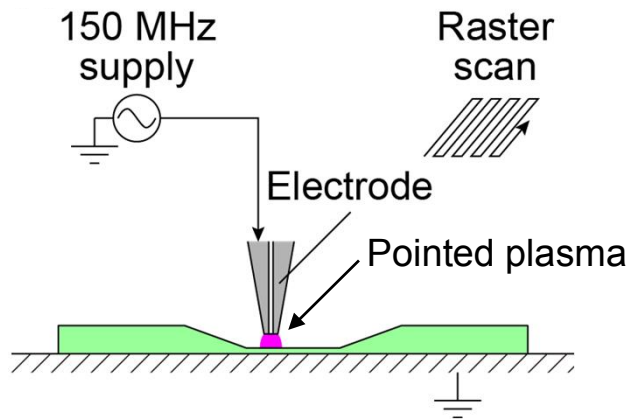
Enables access to time zero

Use of channel cuts:

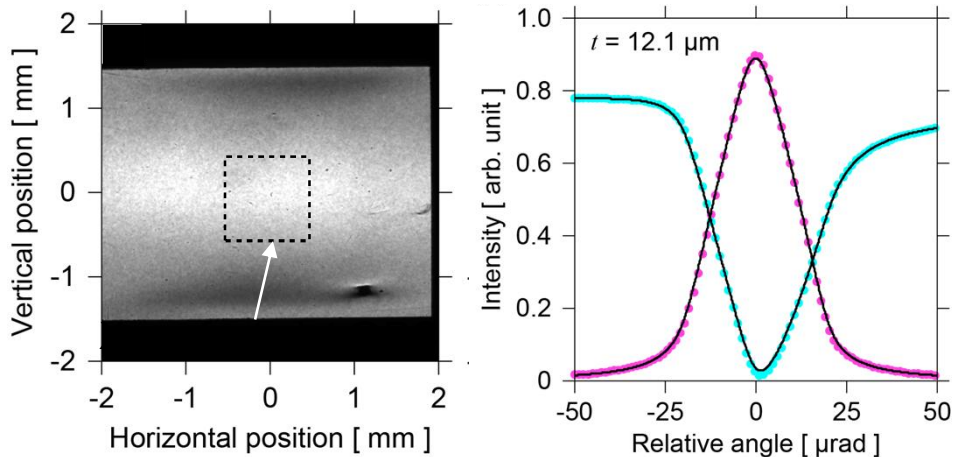
Much stabilized operation

Key optical devices

Thin crystal beam splitter/merger:

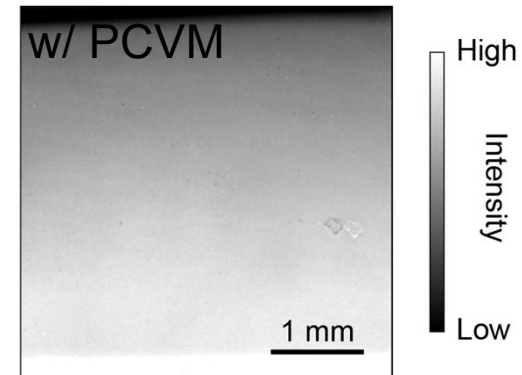
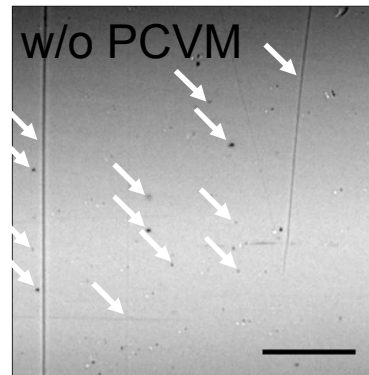
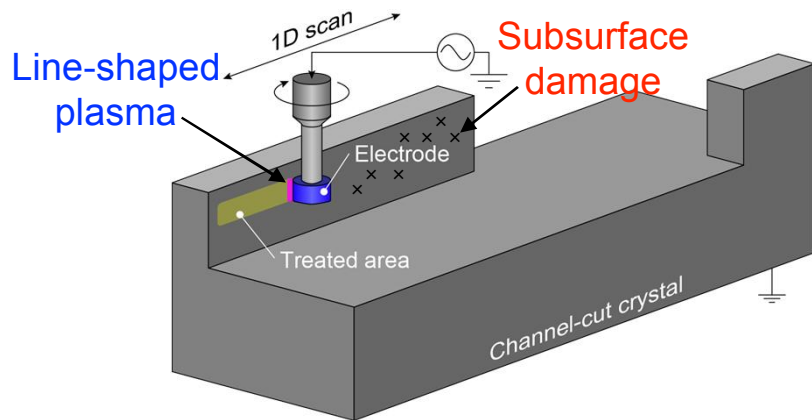


T. Osaka et al., OE **21**, 2823 (2013).



Channel cut crystals:

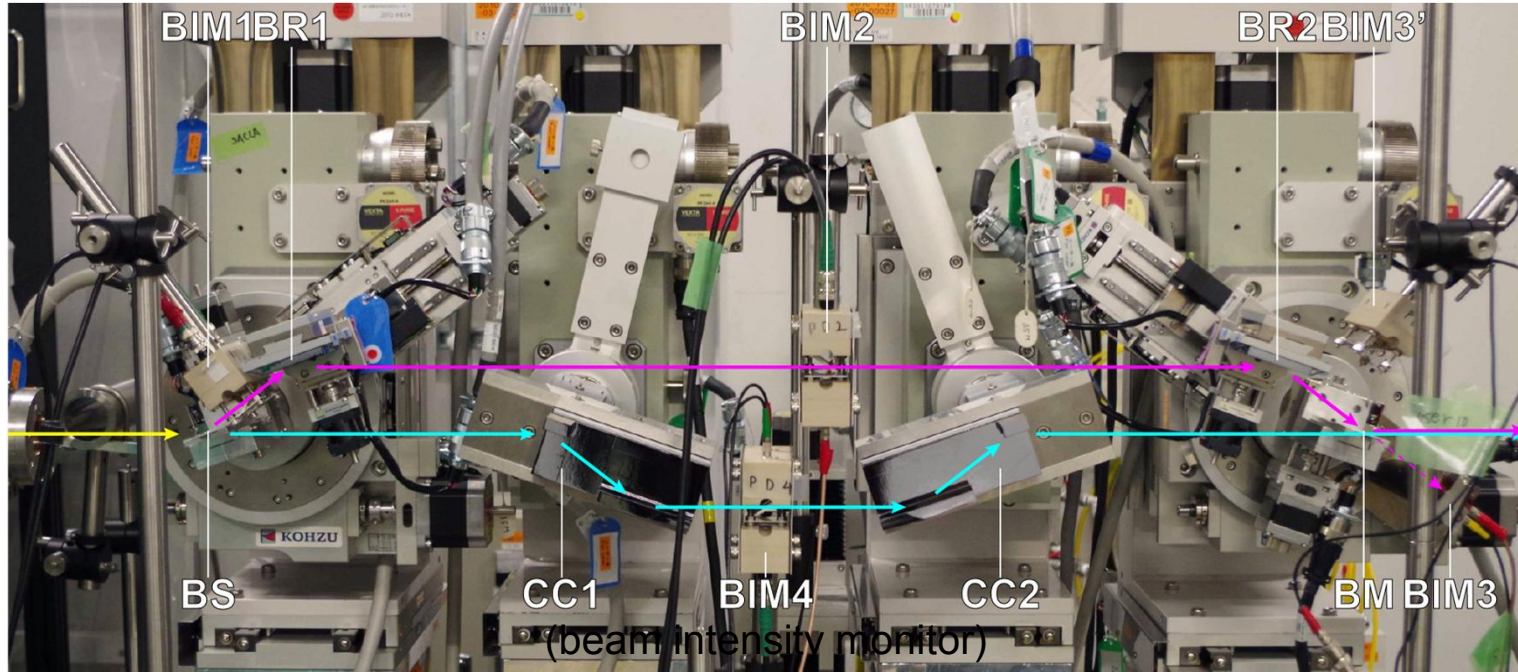
T. Hirano, T. Osaka et al., in reviewed.



Both crystal devices were fabricated using a plasma etching technique.

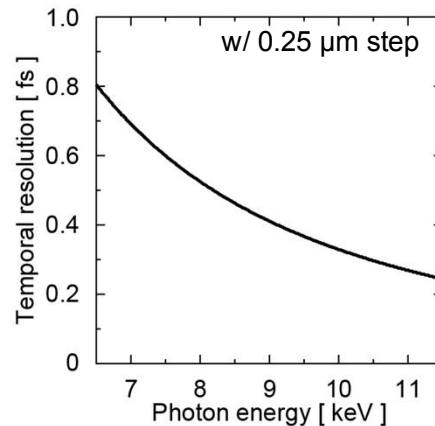
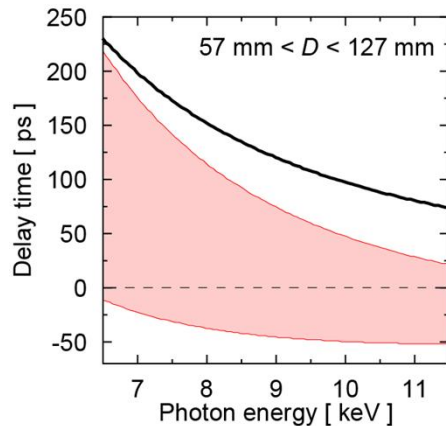
PCVM: non-physical contact, damage-free, controllable plasma size

Prototype SDO



Built with all commercial components for motion control.

Each intensity diagnostic module consists of thin Kapton film scatter and photodiode.



Photon energy range

6.5 keV ~ 11.5 keV

Delay time range @10 keV

-50 ~ +47 ps w/ <1 fs step
(up to 220 ps @6.5 keV)

Performance test @SPring-8

T. Osaka et al., OE **24**, 9187 (2016)

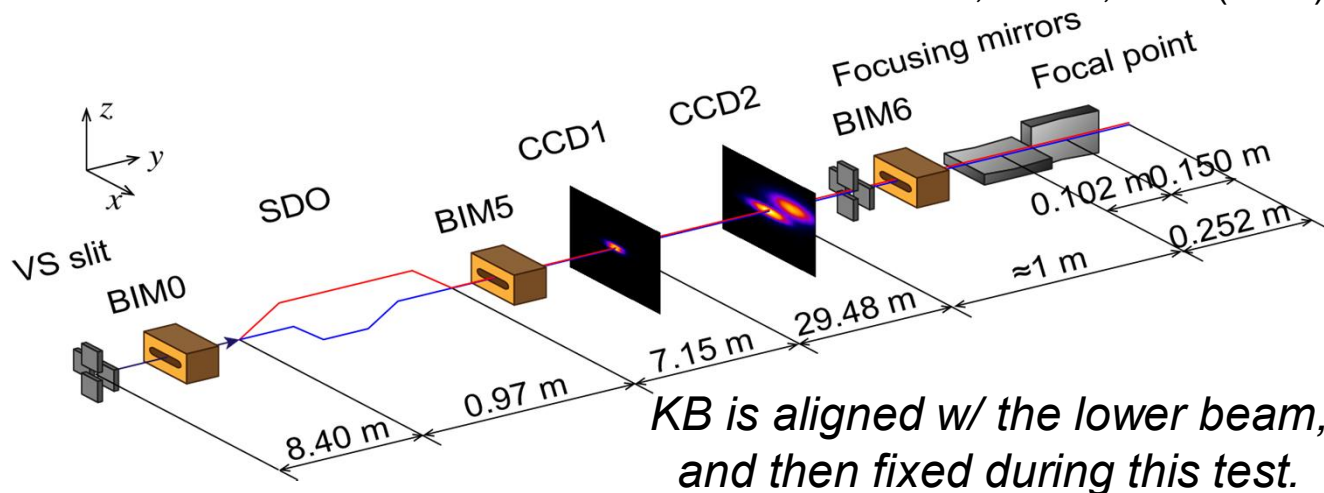
BL29XUL

w/ Si(111) DCM

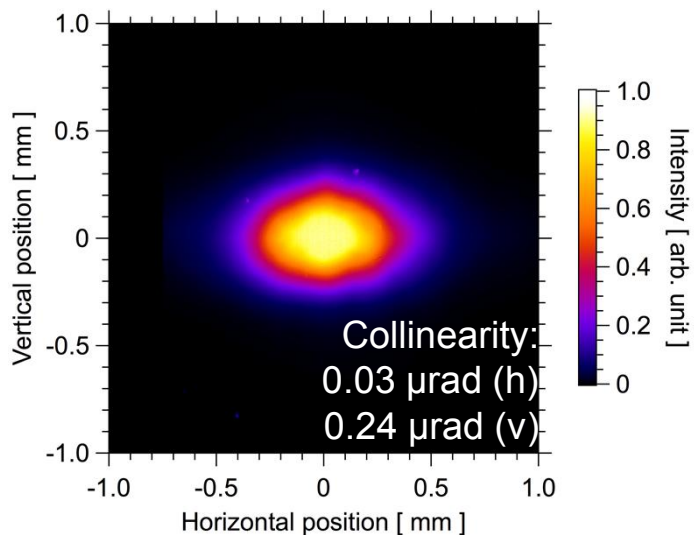
$E = 10 \text{ keV } (\pm 0.35 \text{ eV})$

$\tau \sim +45 \text{ ps}$

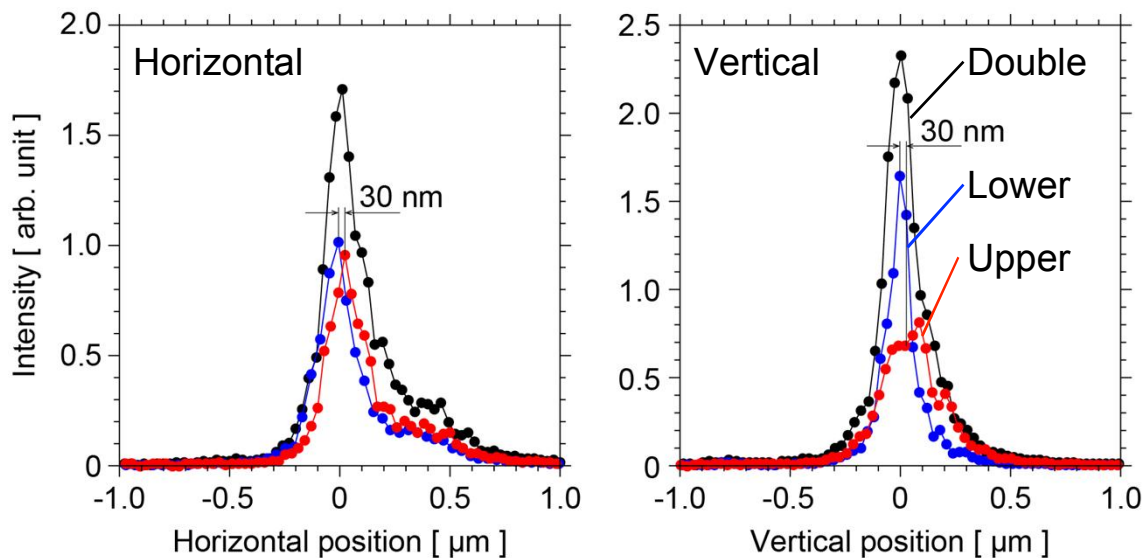
VS slit: $10 \times 10 \text{ } \mu\text{m}^2$



Double beam profile @CCD2



Focal profiles



Sub-urad alignment accuracy achieved

End